

Mechanism for Promoting the Evolution of Lattice Oxygen by the Interaction between V_2O_5 and TiO_2

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The interaction of V_2O_5 with TiO_2 and the evolution of lattice oxygen in V_2O_5/TiO_2 catalysts have been studied by X-ray photoelectron spectroscopy, ultraviolet photoelectron spectroscopy, and thermal gravimetric analysis. The defect surface state associated with oxygen vacancies and the work function of V_2O_5 and TiO_2 are also measured by ultraviolet photoelectron spectroscopy. The results show that the evolution of lattice oxygen takes place mainly near the V_2O_5/TiO_2 interfacial region, and depends strongly on V_2O_5 content and the atmosphere in which the thermal gravimetric analysis is carried out. The defect surface state associated with oxygen vacancies is about 1 and 2.7 eV above the top edge of the valence band for V_2O_5 and TiO_2 , respectively. A model for promoting the evolution of lattice oxygen is proposed on the basis of the energy band structure at the interface of V_2O_5 and TiO_2 . The promotive action is probably due to the bending of the energy band at the interface of V_2O_5 and TiO_2 , which draws the defect surface state of V_2O_5 closer to the valence band of V_2O_5 . As a result, the probability of electron exchange between the defect surface state and the valence band of V_2O_5 increases, and the negative charges on the lattice oxygen ions become easy to remove, thus promoting the evolution of lattice oxygen. In addition, the impurity energy levels arising from vanadium ions in TiO_2 at the interface probably also exchange electrons with the valence band of V_2O_5 , resulting in promotion of the evolution of lattice oxygen. © 1988 Academic Press, Inc.

INTRODUCTION

It is generally agreed that the activity of molecular oxygen in oxidation reactions is rather low, and in almost all good selective oxidation catalysts the lattice oxygen is given up to the reactant, to be replaced in another step of the reaction by adsorption of oxygen from the gas phase (1–6). Participation of the lattice oxygen in the oxidation reaction has been proved by isotopic exchange experiments (5) and by oxidation of anthracene to anthraquinone by vanadium oxide in the absence of gaseous oxygen (6). Obviously, knowledge of mechanism of lattice oxygen evolution is very helpful in gaining an understanding of the catalytic oxidation mechanism.

The evolution of lattice oxygen in metal oxide catalysts is usually promoted by the interaction between metal oxides. For instance, it has been found that both the

reduction of V_2O_5 , or the evolution of lattice oxygen, and the transformation of anatase TiO_2 into rutile are promoted by the interaction between V_2O_5 and TiO_2 (7–11).

Many studies have been devoted to investigation of the mechanism by which TiO_2 modifies the properties of supported V_2O_5 , but the mechanism is still not yet well understood (12, 13). Inomata *et al.* (7) attribute this phenomenon to the selective exposure of the (010) planes of V_2O_5 , in agreement with Vejux and Courtine (10), who suggested that the special properties of V_2O_5/TiO_2 catalysts arise from the close match in crystallographic pattern between the (010) planes of V_2O_5 and the (001) or (010) planes of the TiO_2 anatase. Kozłowski *et al.* (13) attribute this behavior to the intrinsic disorder of surface vanadia species on the TiO_2 surface. Several other authors proposed that the TiO_2 anatase modifies the properties of the supported vanadia phase

by forming a complete monolayer of surface vanadia species coordinated to the TiO_2 support (9, 11, 13–15). However, some researchers (16, 17) have directly observed the high-resolution lattice image obtained by electron microscopy, and have not found a monolayer of vanadia species coordinated to the titania support.

Obviously, there are several points of view of the mechanism by which TiO_2 modifies the properties of supported V_2O_5 . Furthermore, almost all the above mechanisms are based on structural considerations.

The present paper reports the studies of the interaction between V_2O_5 and TiO_2 and the evolution of lattice oxygen by means of X-ray photoelectron spectroscopy (XPS), ultraviolet photoelectron spectroscopy (UPS), and thermal gravimetric analysis (TGA). More attention is paid to the electronic interaction. A mechanism for promoting the evolution of lattice oxygen is proposed on the basis of the interfacial energy band structure and defect surface states associated with oxygen vacancies at the interface of V_2O_5 and TiO_2 .

EXPERIMENTAL

Sample preparation has been described in a previous paper (17). Thermal gravimetric analysis was carried out on a Perkin–Elmer TGS-2 thermobalance under a flowing atmosphere of $\text{He}:\text{O}_2 = 1:1$ and He, respectively. The sample loading is 20 mg. After purging with a He stream for 1 h at 400°C , the temperature was raised to 750°C at the rate of $5^\circ\text{C}/\text{min}$.

XPS and UPS were performed on a VGESCALab-5 photoelectron spectrometer, with a vacuum of 10^{-9} – 10^{-10} Torr. $\text{Al } K\alpha$ line and HeI were used as the exciting source for XPS and UPS, respectively. The powder samples were pressed into wafer form.

The V_2O_5 and TiO_2 samples were bombarded slightly with an Ar^+ ion beam (1 kV, $5 \mu\text{A}$, 2 min) to remove surface contamination, and then annealed at 400°C for 10 min. The UPS spectra were taken at 400°C

which is closer to the catalytic reaction temperature. Ion bombardment on a metal oxide surface usually removes oxygen preferentially resulting in a reduced metal-rich surface. The annealing at several hundred degrees centigrade after ion bombardment would help to restore the surface to bulk stoichiometry by diffusion of oxygen ions from the bulk (19). After annealing, a certain amount of oxygen vacancies still exist on the surface; these are needed to measure the defect surface state. The sample was isolated from ground and biased by a negative voltage of -3.0 V for work function measurement by UPS.

The surface oxygen concentration has been calculated by using $C_x = (A_x R_x / S_x) / \Sigma(A_x R_x / S_x)$, where A_x is the area under the XPS peak for the element x , R_x is the count rate setting, S_x is the sensitivity factor for the specific photoelectron of element x , Σ denotes the summation for all elements included in samples.

Relative sensitivity factors for $\text{V}2p$, $\text{Ti}2p$, and $\text{O}1s$ photoelectrons of 3.15, 1.9, and 1, respectively, have been obtained in our experiment.

RESULTS AND DISCUSSION

Figure 1 shows the surface atom percentage concentration of oxygen calculated from quantitative XPS analysis as a function of V_2O_5 content for a series of catalytic

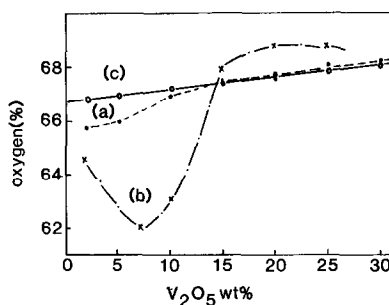


FIG. 1. Surface oxygen percentage concentration obtained from quantitative XPS analysis as a function of V_2O_5 content. (a) Catalytic samples. (b) After TGA experiment in $\text{He}:\text{O}_2 = 1:1$ atmosphere. (c) Calculated from a $\text{V}_2\text{O}_5 + \text{TiO}_2$ mixture.

samples before (a) and after (b) TGA experiments, which were carried out in a $He : O_2 = 1 : 1$ atmosphere. For comparison, the surface oxygen concentrations calculated for a $V_2O_5 + TiO_2$ mixture are also shown in Fig. 1c. In Fig. 1 it should be noted that the surface oxygen concentration depends strongly on V_2O_5 content and the sample processing conditions such as temperature and atmosphere. For low V_2O_5 content, the surface oxygen concentration of the catalytic sample is lower than that calculated from the mixture. After the TGA experiment, the surface oxygen concentration drops much lower, reaching a minimum at about 7 wt% V_2O_5 content. For V_2O_5 content above 15 wt%, the surface oxygen concentration of catalytic samples before TGA is basically the same as that of the mixture; it is even higher after TGA experiments. The results indicate that the V_2O_5 near the interface is slightly reduced during sample preparation ($450^\circ C$, 4 h in air) and further reduced during the TGA experiment. However, away from the interface, the V_2O_5 is not reduced, and even absorbs gas-phase oxygen during TGA experiments. The same phenomenon has been observed for pure V_2O_5 , which increases in weight during TGA experiments in a $He : O_2 = 1 : 1$ atmosphere.

Figures 2a and b show the weight loss for each gram of V_2O_5 in V_2O_5/TiO_2 catalysts as a function of V_2O_5 content for TGA experiments in $He : O_2 = 1 : 1$ and He atmospheres, respectively. It can be seen that the weight loss is strongly dependent on V_2O_5 content and the partial pressure of oxygen in the atmosphere in which the TGA experiments are carried out. The weight loss initially increases with V_2O_5 content, passes through a maximum, then decreases rapidly with increasing V_2O_5 content. The maximum weight loss is at about 7–10 wt% for TGA experiments in $He : O_2 = 1 : 1$ and at much higher V_2O_5 content for TGA experiments in He atmosphere.

The above results may be explained as follows: Both the reduction in surface oxy-

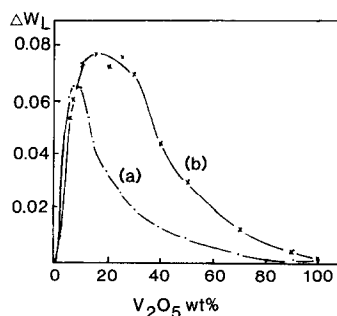


FIG. 2. Weight loss ΔW_L (in percent) per gram of V_2O_5 in catalysts in TGA experiments as a function of V_2O_5 content. (a) In $He : O_2 = 1 : 1$ atmosphere. (b) In He atmosphere.

gen concentration and the weight loss of catalytic samples in TGA experiments arise from the evolution of lattice oxygen, which is promoted by the interfacial interaction between V_2O_5 and TiO_2 . At low V_2O_5 content, vanadia species are well dispersed on the TiO_2 surface, the coverage and thickness of vanadium oxide increase with V_2O_5 content up to 7–10 wt%, the surface V_2O_5 is therefore effectively reduced due to the interfacial interaction, and so the surface oxygen concentration decreases with increasing V_2O_5 content up to 7–10 wt%. Thereafter, any further increase in V_2O_5 content leads mainly to accumulation and thickening of vanadium oxide, which lead to interfacial interaction between surface V_2O_5 and TiO_2 ; therefore, the promotion for evolving lattice oxygen becomes weaker and weaker with increasing V_2O_5 content (17, 18). As a result, the surface oxygen concentration begins to increase, and the weight loss in TGA experiments begins to decrease, with increasing V_2O_5 content. When the thickness of vanadium oxide extends beyond the interaction range of V_2O_5 and TiO_2 , which probably occurs above 15 wt% V_2O_5 content, the promotion for the evolution of lattice oxygen basically disappears, the surface V_2O_5 in catalysts behaves like pure V_2O_5 , so the surface oxygen concentration even increases in TGA experiments for V_2O_5 content above

15 wt%, as mentioned above. The detailed calculation of the dispersion, coverage, and thickness of vanadia species in V_2O_5/TiO_2 catalysts has already been given (17).

According to the preceding analysis, the curve of weight loss in Fig. 2a should be basically flat for V_2O_5 content below 7–10 wt%. However, the experimental result is different from that expected, probably because some lattice oxygen evolved during the sample preparation, as has been discussed.

In all metal oxides, lattice oxygen ions are negatively charged, and form strong bonds with metal cations. The process of evolution of lattice oxygen must involve removal of valence electrons from lattice oxygen ions. From the energy band view point, which involves injecting holes from appropriate energy levels to the valence band which is derived predominantly from O_L^{2-} ions. This process can be represented as $2h^+ + O_L^{2-} \rightarrow \frac{1}{2}O_2$, where O_L^{2-} is a lattice oxygen ion of a solid oxide, and h^+ is the hole.

The results of both XPS and TGA experiments show that the evolution of lattice oxygen takes place mainly in a vanadia layer of certain thickness near the interface of V_2O_5 and TiO_2 , beyond which the V_2O_5 has no activity for the evolution of lattice oxygen. V_2O_5 and TiO_2 are transition metal oxide semiconductors, and belong to non-stoichiometric compounds, their surface composition and oxygen vacancies depending on the equilibrium between the lattice and the gas-phase constituent or the partial pressure of oxygen. The oxygen vacancies in the lattice play an important role in electron exchange. Therefore, it seems reasonable to explain the evolution of lattice oxygen in terms of the interfacial energy band structure and defect surface state associated with oxygen vacancies.

The defect surface state and work function of V_2O_5 and TiO_2 can be measured by using UPS. Figure 3 shows the UPS spectra of V_2O_5 and TiO_2 . From Fig. 3, it is known that the work function of V_2O_5 (6 eV) is

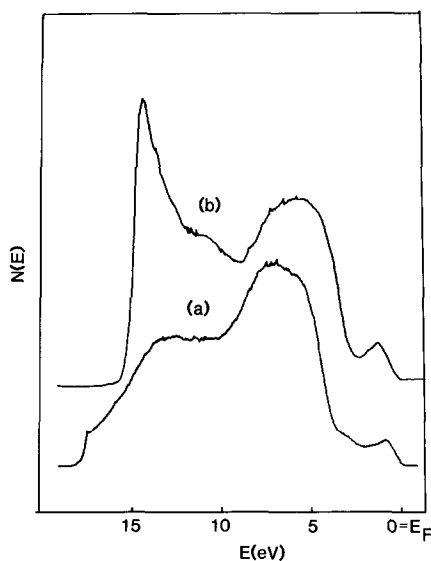


FIG. 3. UPS spectra for (a) TiO_2 and (b) V_2O_5 taken at 400°C. Samples were bombarded for 2 min with 1 kV of a 5- μ A Ar^+ ion beam, and then annealed at 400°C for 10 min. The curves are aligned at E_F .

greater than that of TiO_2 (4.6 eV) as calculated with the formula of Jacobi *et al.* (20). The UPS spectra contain a small peak with a maximum at an energy about 1 and 2.7 eV above the top edge of the valence for V_2O_5 and TiO_2 , respectively, which possibly is ascribed to the defect surface state associated with oxygen vacancies. Much work on defect surface state of TiO_2 and $SrTiO_3$ has been done by Henrich (19).

At the interface of V_2O_5 and TiO_2 the oxygen vacancies and defect surface state should exist, especially at high temperature. Figure 4 shows the UPS spectra of V_2O_5 and a 10 wt% V_2O_5/TiO_2 catalyst sample. The UPS peak due to the defect surface state can also be clearly seen for the unbombarded samples at 400°C. At room temperature, this peak is not obvious, probably because of the low density of oxygen vacancies and surface contamination.

Owing to the fact that the work function of V_2O_5 is greater than that of TiO_2 , according to the semiconductor interfacial theory, the energy band of V_2O_5 will bend down at the interface of V_2O_5 and TiO_2 . Figure 5

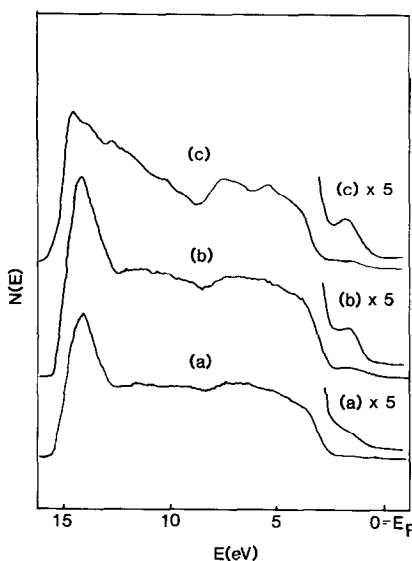


FIG. 4. UPS spectra for (a) V₂O₅ at room temperature, (b) V₂O₅ at 400°C, and (c) 10 wt% V₂O₅/TiO₂ catalyst at 400°C.

shows a schematic diagram of the interfacial energy band structure of V₂O₅ and TiO₂ and the defect surface states, which are about 1 and 2.7 eV above the top of the valence band for V₂O₅ and TiO₂, respectively. In addition, the densities and energy of the defect surface state strongly affect the interfacial energy band structure: if the densities of the defect surface states of V₂O₅ and TiO₂ are high enough, the Fermi energy level might be pinned at their own defect surface state. In this case, the Fermi energy level of TiO₂ is much higher than that of V₂O₅. However, at the interface of V₂O₅ and TiO₂ they should have the same Fermi energy level; thus the energy band of V₂O₅ should also bend down. The bending of the V₂O₅ energy band brings the energy levels of the defect surface states of V₂O₅ near the interface close to the valence band of bulk V₂O₅ as shown in Fig. 5. As a result, the probabilities of electron exchange between the defect surface state of V₂O₅ and the valence band of bulk V₂O₅ increase, or the probabilities of injecting holes from the defect surface state to the

valence band of V₂O₅ increase; thus the negative charges on lattice oxygen ions become easily removable, and the evolution of lattice oxygen is promoted.

In addition, Sakata (21) reported that in V_xTi_{1-x}O₂ ($x = 2.5 \times 10^{-3}$), the excess 3d electrons of vanadium ions form impurity levels just above the top of the valence band is about 0.6 eV. It has also been reported that after a 650°C calcination treatment of the V₂O₅/TiO₂ catalyst, approximately 6% of the titania is present as solid solution V_xTi_{1-x}O₂ (rutile) at the interface of V₂O₅ and TiO₂ (11), and the maximum molar fraction of V⁴⁺ ions able to be dissolved is about 0.04 (22). These V ions can be considered an impurity. Therefore, the impurity energy level mentioned above exists at the interface of V₂O₅ and TiO₂, especially at high temperature. It can probably also exchange electrons with the valence band of V₂O₅, leading to increased evolution of lattice oxygen.

From the preceding model, it can be expected that any change in the state of the TiO₂ surface before sample preparation or during formation of the V₂O₅/TiO₂ interface probably brings about changes in the interfacial energy band structure, and therefore

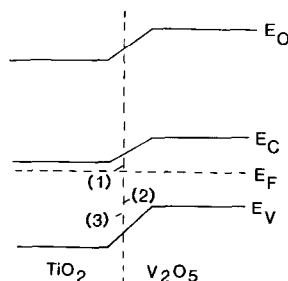


FIG. 5. Scheme of the energy band structure at the V₂O₅/TiO₂ interface. The bulk bandgaps are 2.5 and 3.05 eV for V₂O₅ and TiO₂, respectively. (1) and (2) represent the defect surface states associated with oxygen vacancies for TiO₂ and V₂O₅, respectively. (3) represents impurity energy levels induced by vanadia ions in TiO₂ at the interface. E₀, E_c, E_v, and E_F represent the vacuum energy level, conduction band edge, valence band edge, and Fermi energy level, respectively.

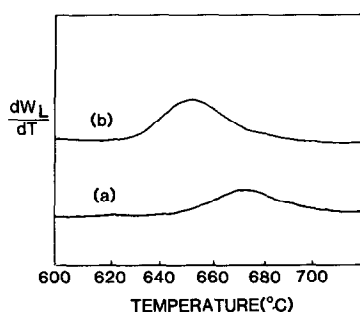


FIG. 6. Derivative curve of weight loss for 7 wt% V_2O_5/TiO_2 catalysts in the TGA experiments carried out in He atmosphere. (a) TiO_2 was not pretreated. (b) TiO_2 was pretreated by impregnation with 1 N NH_4OH aqueous solution.

in the evolution of lattice oxygen. We changed the state of the TiO_2 surface by impregnating TiO_2 powder with 1 N NH_4OH aqueous solution before sample preparation and have observed its effect on the evolution of lattice oxygen. Figure 6 shows the derivative curve of weight loss in TGA experiments for pretreated and untreated 7 wt% V_2O_5/TiO_2 catalytic samples. It can be seen that pretreatment of TiO_2 with NH_4OH aqueous solution decreases the temperature of evolving lattice oxygen about $20^\circ C$. This is probably due to the fact that the pretreatment of TiO_2 decreases its work function, thus increasing the probability of electron exchange between the defect surface state and the valence band of V_2O_5 .

The densities of the defect surface state can be changed by heating the metal oxide samples in a different atmosphere. Therefore, the evolution of lattice oxygen should be affected by the atmosphere in which the TGA experiment is carried out. Figure 2 shows that the maximum weight loss occurs at different V_2O_5 contents for TGA experiments in $He:O_2 = 1:1$ and in He atmosphere. This phenomenon can also be explained on the basis of the above model. The melting point of V_2O_5 is about $690^\circ C$ and the temperature range of the TGA experiment $500\text{--}750^\circ C$. It can be imagined that during the TGA experiments a new

interface forms in addition to the original ones, as shown in Fig. 7, which also promotes the evolution of lattice oxygen in TGA experiments. However, we should remember that the condition for the formation of a new interface is different for TGA experiments in $He:O_2 = 1:1$ and He atmospheres, which is also different from that of the original interface. The partial pressure of oxygen in a $He:O_2 = 1:1$ atmosphere is much higher than in air (the original interface is formed in air) and approach zero in a He atmosphere. Clearly, the number of oxygen vacancies and the densities of defect surface states associated with oxygen vacancies at the new interface of V_2O_5 and TiO_2 are much higher for the new interface formed in He than in $He:O_2 = 1:1$ atmosphere. For the TGA experiments in $He:O_2 = 1:1$ atmosphere the densities of defect surface states are very low due to the high partial pressure of oxygen. The promotive action for evolution of lattice oxygen is caused mainly by the original interface, so the maximum weight loss is at about 10 wt% V_2O_5 content, as has been discussed. However, for the TGA experiments in He atmosphere, the densities of defect surface states at the new V_2O_5/TiO_2 interface are high due to the very low

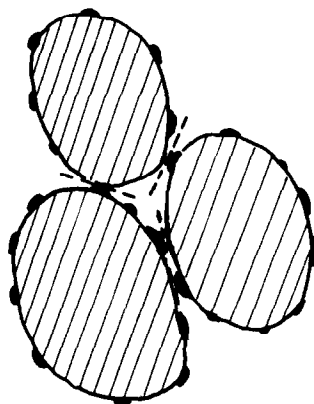


FIG. 7. Schematic diagram for the formation of new V_2O_5/TiO_2 interfaces between different catalytic particles during TGA experiments. \odot , TiO_2 particles; \bullet , V_2O_5 supported on TiO_2 surface; ---, new interfaces.

partial pressure of oxygen during formation of the new interface. The high densities of defect surface states at the new interface will affect the evolution of lattice oxygen in two aspects: (1) The increase in density of defect surface states directly increases the probability of electron exchange between the defect surface state and the valence band of V_2O_5 . (2) The Fermi energy levels of V_2O_5 and TiO_2 are probably pinned at their own defect surface states, which makes the energy band of V_2O_5 near the interface bend down more, and brings the defect surface state of V_2O_5 closer to its bulk valence band at the interface, thus leading to increased electron exchange probabilities between the defect surface state and the valence band of bulk V_2O_5 . The new interface therefore plays an even more important role in the evolution of lattice oxygen than the original interface. The new and original interfaces together make the maximum weight loss shift to high V_2O_5 content for TGA experiments in He atmosphere. These two results provide evidence for our model.

In summary, the evolution of lattice oxygen of V_2O_5/TiO_2 catalysts is strongly dependent on V_2O_5 content and on the atmosphere in which the TGA experiments are carried out, and is promoted by interfacial interaction between V_2O_5 and TiO_2 . The defect surface states associated with oxygen vacancies play a very important role in promoting the evolution of lattice oxygen. The interfacial interaction of V_2O_5 with TiO_2 brings the defect surface state of V_2O_5 near the interface closer to the valence band of bulk V_2O_5 , which results in an increase in the probability of electron exchange between the defect surface state of V_2O_5 and the valence band of bulk V_2O_5 . The negative charges in lattice oxygen ions thus become easily removable, leading finally to promotion of the evolution of lat-

tice oxygen. Work is now in progress to seek more proof for this model.

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